- 2024 ADRIAN M. IONESCU Professor, Ecole Polytechnique Fédérale de Lausanne, Lausanne, Switzerland
- 2023 JOHN ROBERTSON Professor (Retired), Cambridge University, Cambridge, Cambridgeshire, United Kingdom

"For leadership and contributions to the field of energy-efficient steep slope devices and technologies."

"For theoretical contributions to the integration of high-k oxides on semiconductors."

- 2022 SIMON DELEONIBUS Chief Scientist (Retired), CEA, LETI, Grenoble, France
- 2021 JESUS DEL ALAMO Donner Professor and Professor of Electrical Engineering, Massachusetts Institute of Technology, Cambridge, Massachusetts, USA

nanoscale CMOS device and process technologies."

"For contributions to and leadership in

"For leadership in and contributions to InGaAs- and GaN-based field-effect transistor technology."

2020 JAMES H. STATHIS Principal Research Staff Member, IBM Research, Yorktown Heights, New York, USA "For contributions to the understanding of gate dielectric reliability and its application to transistor scaling."

#### AND

ERNEST YUE WU Senior Technical Staff Member, IBM Research, Albany, New York, USA

2019 DANIEL C. EDELSTEIN IBM Fellow, IBM T.J. Watson Research Center, Yorktown Heights, New York, USA

AND

ALFRED GRILL IBM Fellow, IBM T.J. Watson Research Center, Yorktown Heights, New York, USA "For contributions to manufacturable, reliable, and scalable Cu interconnect and low-k dielectric technology for CMOS."

CHAO-KUN HU Research Staff Member, IBM T.J. Watson Research Center, Yorktown Heights, New York, USA

2018 SIEGFRIED SELBERHERR Professor, Vienna University of Technology, Institute for Microelectronics, Vienna, Austria "For pioneering contributions to Technology Computer Aided Design."

- 2017 GUIDO GROESENEKEN Professor, Catholic University of Leuven, and Fellow, IMEC, Leuven, Belgium
- 2016 AKIRA TORIUMI Professor, The University of Tokyo, Tokyo, Japan
- 2015 HIROSHI IWAI Professor, Tokyo Institute of Technology, Yokohama, Kangawa, Japan
- 2014 MARTIN VAN DEN BRINK Vice President, ASML, Veldhoven, The Netherlands
- 2013 GIORGIO BACCARANI Full Professor, University of Bologna, Bologna, Italy
- 2012 YAN BORODOVSKY Intel Senior Fellow, Director of Advanced Lithography, Intel Corporation, Hillsboro, OR, USA AND

SAM SIVAKUMAR Intel Fellow, Director of Lithography, Intel Corporation, Hillsboro, OR, USA

2011 MASSIMO V. FISCHETTI Professor, University of Massachusetts, Amherst, MA, USA "For contributions to the characterization and understanding of the reliability physics of advanced MOSFET nanodevices."

"For contributions to CMOS device design from materials engineering to device physics."

"For contributions to the scaling of CMOS devices."

"For designing new lithography tool concepts and bringing these to the market, enabling micrometer to nanometer imaging."

"For contributions to scaling theory and modeling of metal oxide semiconductor (MOS) devices."

"For contributions to developing and implementing innovative lithographic and patterning equipment and processes to enable cost-effective scaling for logic technologies."

"For contributions to the fundamental understanding of the physics, design and scaling of nanosized electronic devices."

AND DAVID J. FRANK Research Staff Member, IBM T. J. Watson Research Center, Yorktown Heights, NY, USA AND STEVEN E. LAUX Research Staff Member, IBM T. J. Watson Research Center, Yorktown Heights, NY, USA 2010 GHAVAM SHAHIDI "For contributions to and leadership in the IBM Fellow Director of Silicon Tech development of silicon-on-insulator CMOS IBM TJ Watson Research Ctr technology." Yorktown Heights, NY, USA 2009 BURN JENG LIN "For contributions to immersion lithography Senior Director of Micropatterning for the manufacture of integrated circuit Division, TSMC, Ltd. Hsin-Chu, devices." Taiwan 2008 MICHEL BRUEL "For inventing Smart Cut<sup>™</sup> layer transfer Deputy Director of CEA-LETI, technology that enabled widespread Director of Research, CEA, Cedex, adoption of SOI for CMOS circuits." France 2007 SANDIP TIWARI "For pioneering contributions to nano-Professor, Electrical and Computer crystal memories and to quantum effect Engineering, Cornell University devices." Ithaca, NY 2006 SUSUMU NAMBA "For contributions to ion-beam and optical Professor, Nagasaki Institute of technologies for application to **Applied Science** semiconductor devices." Nagasaki, Japan 2005 WILLIAM G. OLDHAM "For pioneering contributions to lithographic Professor Emeritus, University of engineering and to high-density isolation California, Berkeley technology." Berkeley, CA 2004 STEPHEN Y. CHOU "For the invention and development of tools Professor, Department of Electrical for nanoscale patterning, especially Engineering nanoimprint lithography, and for the scaling **Princeton University** of devices into new physical regimes."

2003 ANDREW R. NEUREUTHER Professor, EECS, University of

Princeton, NJ

"For pioneering contributions to modeling and simulation of the lithographic materials,

	California, Berkeley, CA	processes, and tools used in microelectronics manufacturing."
2002	MARK LUNDSTROM SUPRIYO DATTA Purdue University, West Lafayette, IN	"For significant contributions to the understanding and innovative simulation of nano-scale electronic devices."
2001	R. FABIAN W. PEASE Stanford University Stanford, CA	"For advancing high resolution patterning technologies, high performance thermal management, and scanning electron microscopy for microelectronics."
2000	ROBERT E. FONTANA IBM Almaden Research Center San Jose, CA	"For contributions to micro fabrication techniques for the manufacture of thin film and giant magnetoresistive heads used in hard disk drives."
1999	DAVID K. FERRY Arizona State Univ., Tempe, AZ	"For fundamental contributions to the theory and development of nanostructured devices."
1998	ROGER T. HOWE RICHARD S. MULLER University of California, Berkeley, CA	"For leadership and pioneering contributions to the field of microelectromechanical systems."
1997	DIETER P. KERN GEORGE A. SAI-HALASZ MATTHEW R. WORDEMAN IBM Research, Yorktown Heights, NY	"For the development of sub-0.1 micron MOSFET devices and circuits."
1996	MITSUMASA KOYANAGI Tohoku Univ Intell Sys Lab Sendai, Japan	"For pioneering research and development of the three dimensional stacked capacitor DRAM cell."
1995	HENRY I. SMITH MIT, Cambridge, MA	"For contributions to microfabrication science and technology, notably microlithography."
1994	EIJI TAKEDA Hitachi Ltd. Tokyo, Japan	"For pioneering contributions to the characterization and understanding of hot-carrier effects in MOS devices."
1993	TAKAFUMI NAMBU MITSURU IDA	"For the development of the WALKMAN, the realization of a totally new concept of
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KAMON YOSHIYUKI SONY Corporation, Tokyo, Japan

- 1992 DAVID A. THOMPSON IBM Corp. San Jose, CA
- 1991 HIDEO SUNAMI Hitachi, Ltd., Tokyo, Japan
- 1990 ELSE KOOI Philips Research Labs. Sunnyvale, CA
- 1989 SHUN-ICHI IWASAKI Tohoku University, Sendai, Japan
- 1988 IRVING AMES IBM Corp., NY FRANCOIS M. d'HEURLE RICHARD E. HORSTMANN
- 1987 MICHAEL HATZAKIS IBM Corp., Yorktown Heights, NY
- 1986 RICHARD M. WHITE Univ of California, Berkeley, CA
- 1985 ALEC N. BROERS IBM Corporation Hopewell Junction, NY
- 1984 HARRY W. RUBINSTEIN Sprague Electric Co. Grafton, Wisconsin
- 1983 ABE OFFNER Perkin-Elmer Corp. Wilton, CT
- 1982 ROBERT H. DENNARD

miniaturization of consumer electronics."

"For pioneering work in miniature magnetic devices for data storage, including the invention, design and development of thin-film and magnetoresistive recording heads."

"For contributions in the invention and development of the trench capacitor DRAM cell."

"For invention and development of the process for localized oxidation of silicon using a silicon nitride mask, which enabled greatly reduced dimensions in VLSI circuits."

"For contributions to the miniaturization of magnetic recording systems."

"For the invention of electromigration-resistant copper-doped aluminum metallurgy."

"For fundamental contributions to the patterning techniques of submicron electron devices."

"For invention of surface acoustic wave electronic devices for signal processing applications."

"For leadership and pioneering contributions to the technology and applications of electron beams to fine line lithography."

"For early key contributions to the development of printed components and conductors on a common insulating substrate."

"For the invention and design of the optics which made possible the projection lithography systems that were key to advancing integrated circuit manufacture."

"For the invention of the one-transistor

IBM Corp. Yorktown Heights, NY

- 1981 DONALD R. HERRIOTT Bell Labs. Murray Hill, NJ
- 1980 MARCIAN E. HOFF, JR. INTEL Corp. Santa Clara, CA
- 1979 GEOFFREY W. A. DUMMER Worcestershire, England
- AND PHILIP J. FRANKLIN GSA, Federal Supply Service Washington, DC
- 1978 JACK S. KILBY Texas Instrument, Dallas, TX ROBERT N. NOYCE Intel Corporation, Santa Clara, CA

dynamic random access memory cell and for contributions to scaling of MOS devices."

"For key contributions to the development of a practical electron beam system for fabrication of integrated circuit masks and to other aspects of microlithography."

"For the conception and development of the microprocessor."

"For contributions to materials development and fabrication techniques for miniature passive electronic components and assemblies."

"For contributions to miniaturization through inventions and the development of integrated circuits."